

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
1	BRS	L8	41	((first and second) adj (time or step or stage)) same (CMP or "chemical mechanical polishing")) and @pd<=19981104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/07 14:15		0
2	BRS	L19	51	((additive) same (CMP or "chemical mechanical polishing")) and @pd<=19981104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/07 14:20		0
3	BRS	L26	5	((additive) same (surfactant or PEG or triazole) same (CMP or "chemical mechanical polishing")) and @pd<=19981104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/07 14:21		0

	Type	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
1	BRS	2	(decreas\$3 near5 flow near5 (slurry)) same (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/31 19:00		0
2	BRS	202	((first and second) adj (time or step or stage)) same (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/31 19:03		0
3	BRS	41	((first and second) adj (time or step or stage)) same (CMP or "chemical mechanical polishing")) and @pd<=19981104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/31 19:47		0